Electronic Supplementary Material (ESI) for Journal of Materials Chemistry C

Supporting Information

Alkaline-developable Positive-type Photosensitive Polyimide Based on Fluorinated Poly(amic acid) Poly(amic acid), and Fluorinated Diazonaphthoquinone

*Yusuke Inoue, Yuta Saito, Tomoya Higashihara, and Mitsuru Ueda**

Department of Organic and Polymeric Materials, Graduate School of Science and Engineering, Tokyo Institute of Technology, 2-12-1-H-120, O-okayama, Meguro-Ku, Tokyo 152-8552, Japan

[*] To whom correspondence should be addressed. Telephone: +81-3-57342127. Fax: +81-3-57342127. E-mail: ueda.m.ad@m.titech.ac.jp

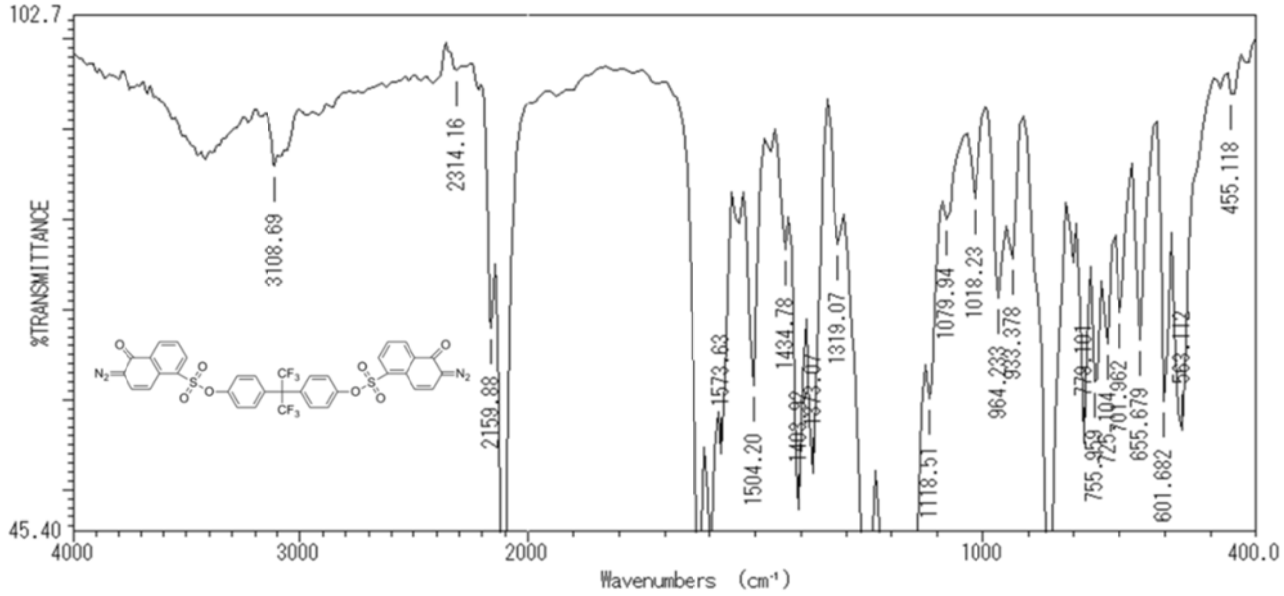

Figure S1. IR spectrum of **FDNQ-1**.

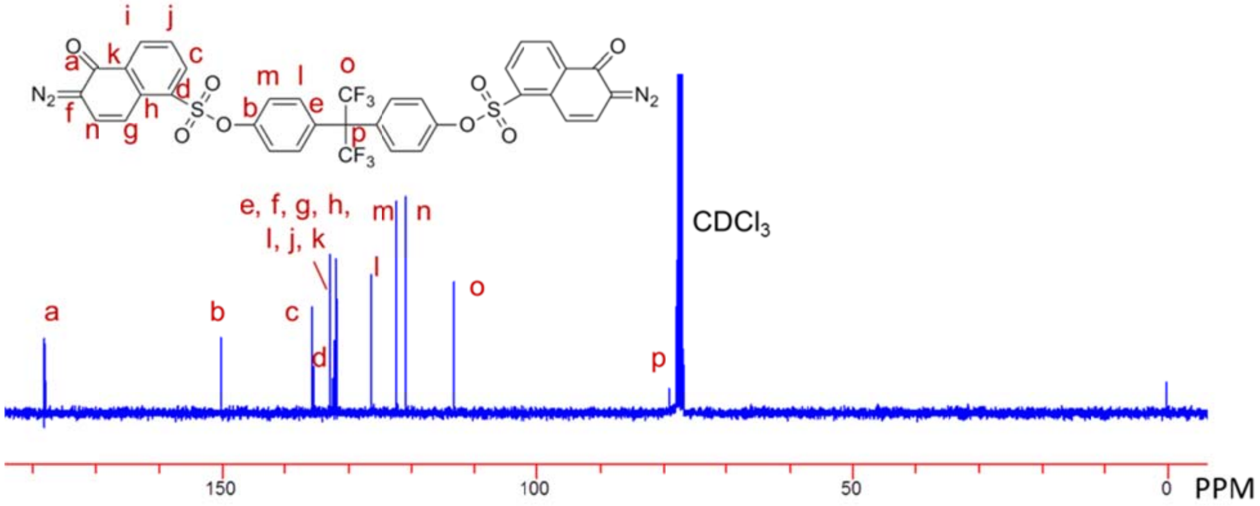

Figure S2. ^{13}C NMR spectrum of **FDNQ-1**.

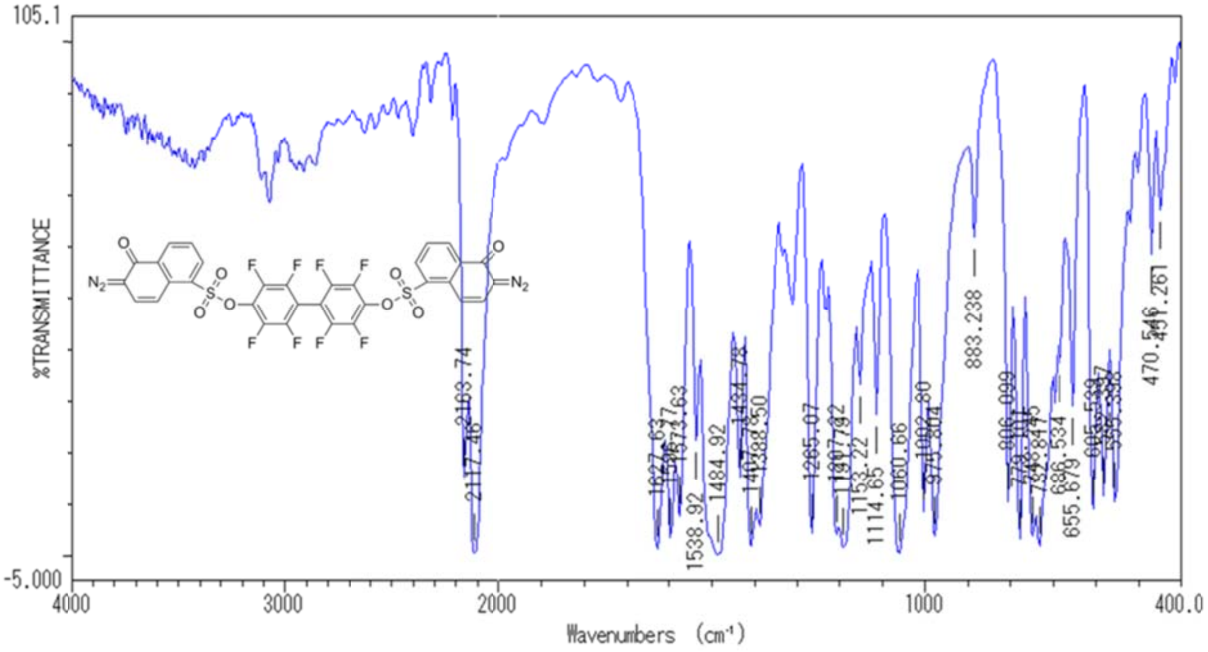

Figure S3. IR spectrum of **FDNQ-2**.

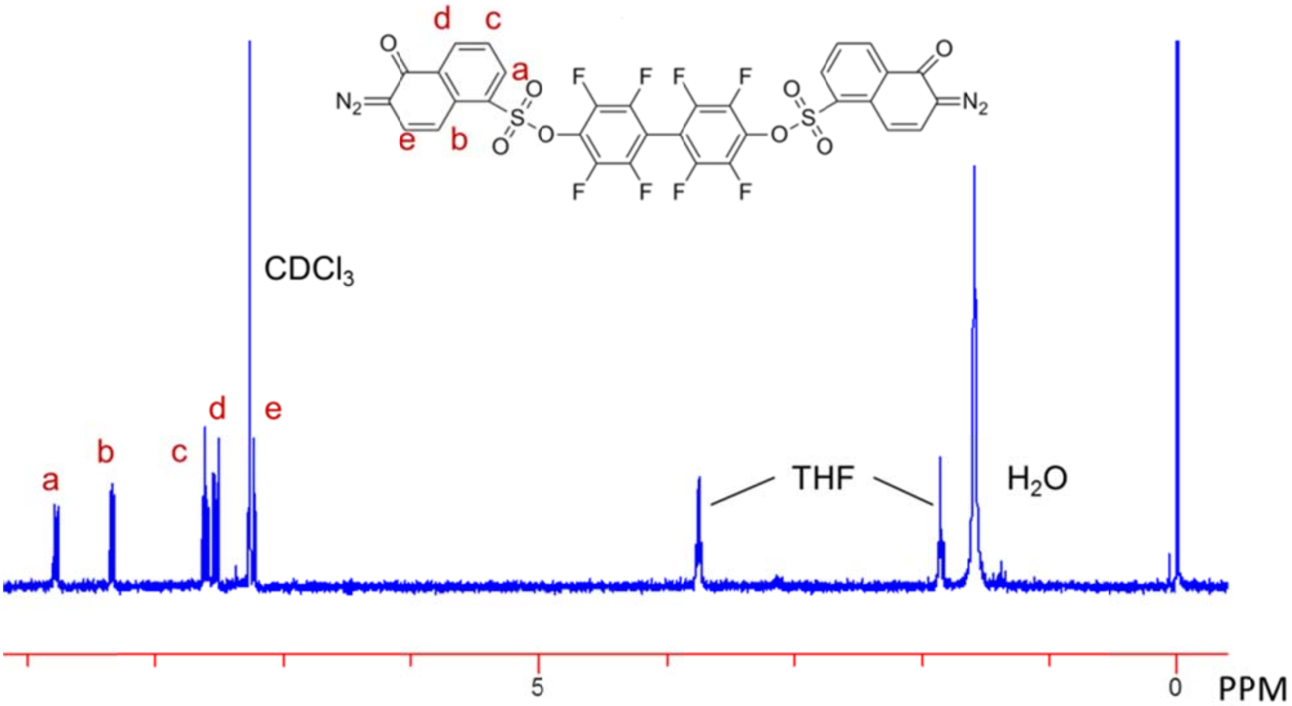

Figure S4. ^{1}H NMR spectrum of **FDNQ-2**.

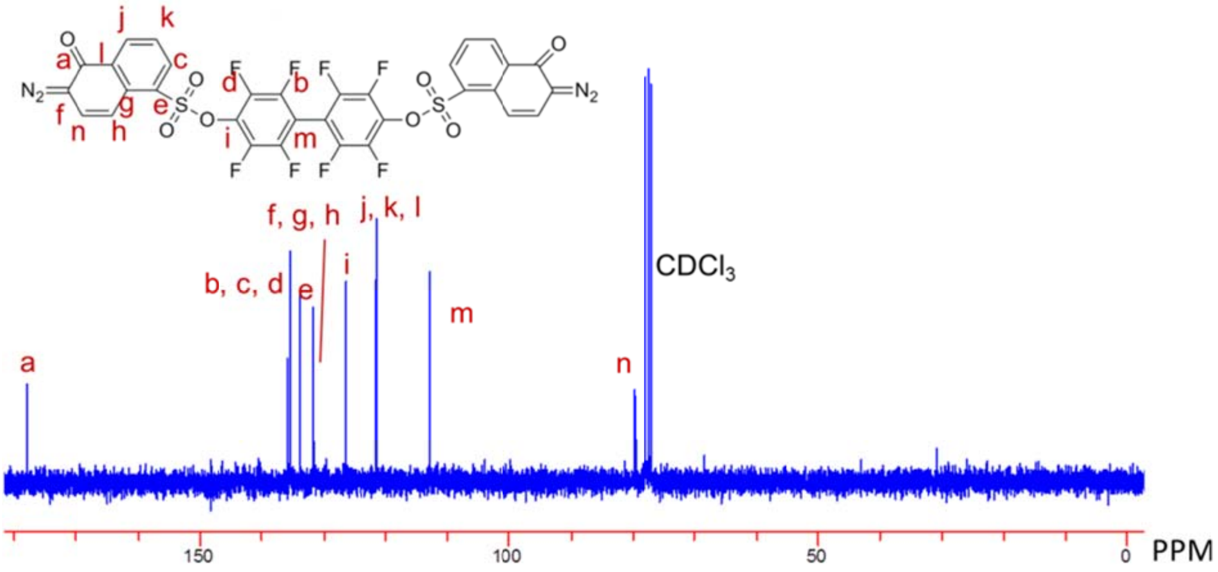

Figure S5. ^{13}C NMR spectrum of **FDNQ-2**.

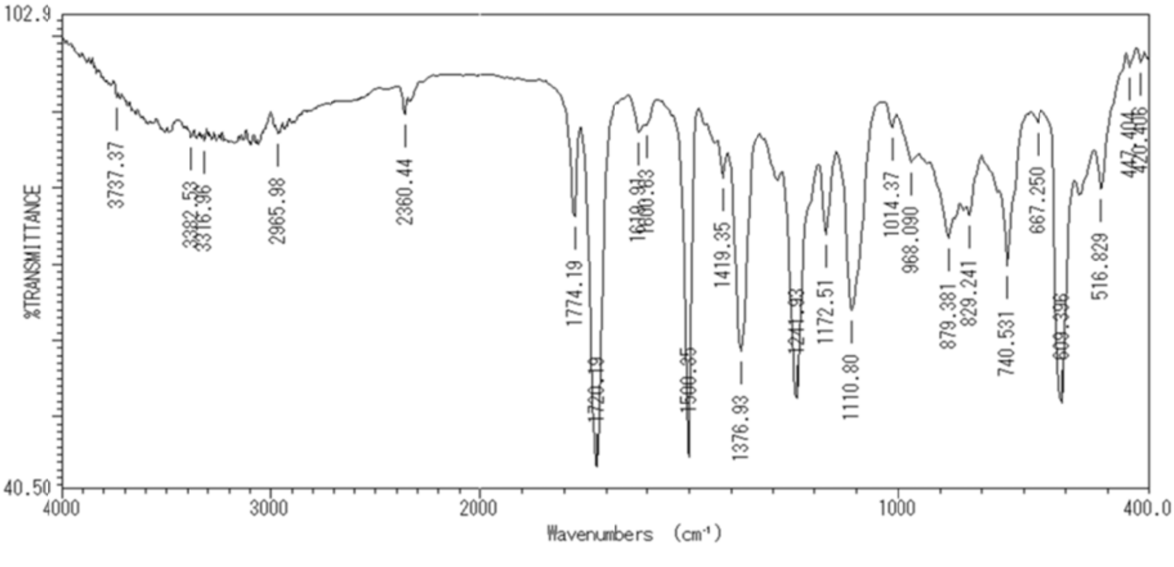

Figure S6. FT-IR spectrum of the PI film.